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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/727,552	12/05/2003	Ian Rippke	42339-198344	7984
26694	7590	06/01/2005	EXAMINER	
VENABLE LLP			NGUYEN, JOSEPH H	
P.O. BOX 34385			ART UNIT	
WASHINGTON, DC 20045-9998			PAPER NUMBER	

2815

DATE MAILED: 06/01/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary

Application No.

10/727,552

Applicant(s)

RIPPKE ET AL.

Examiner

Joseph Nguyen

Art Unit

2815

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) ☒ Responsive to communication(s) filed on 14 March 2005.
- 2a) ☐ This action is FINAL. 2b) ☒ This action is non-final.
- 3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

- 4) ☒ Claim(s) 1-14, 26-33, 35-36 and 38-41 is/are pending in the application.
- 4a) Of the above claim(s) _____ is/are withdrawn from consideration.
- 5) ☒ Claim(s) _____ is/are allowed.
- 6) ☒ Claim(s) 1-, 8, 14, 26-33, 35-36, 38-41 is/are rejected.
- 7) ☒ Claim(s) 9-13 is/are objected to.
- 8) ☐ Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

- 9) ☐ The specification is objected to by the Examiner.
- 10) ☒ The drawing(s) filed on 12 May 2003 is/are: a) ☒ accepted or b) ☐ objected to by the Examiner.
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
- 11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

- 12) ☒ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
- a) ☒ All b) ☐ Some * c) ☐ None of:
- 1) ☒ Certified copies of the priority documents have been received.
 - 2) ☐ Certified copies of the priority documents have been received in Application No. _____.
 - 3) ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

* See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

- 1) ☒ Notice of References Cited (PTO-892)
- 2) ☐ Notice of Draftsperson's Patent Drawing Review (PTO-948)
- 3) ☐ Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)
Paper No(s)/Mail Date _____
- 4) ☐ Interview Summary (PTO-413)
Paper No(s)/Mail Date. _____
- 5) ☐ Notice of Informal Patent Application (PTO-152)
- 6) ☐ Other: _____

DETAILED ACTION

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

Claims 1-3, 5, 6, 8, 26-29, 31, 33, 38 and 39 are rejected under 35 U.S.C. 102(e) as being anticipated by Iwata et al (US 6,876,055 B2).

Regarding claim 1, Iwata et al discloses on figure 10 a device, comprising:

a layer of a first conductivity type 315 (col.21, line 44);

a first transistor 327 disposed in the layer (col. 21, line 51);

a body contact region 322 (Iwata et al. teaches in col. 21, lines 59-62 that a well bias input 330 for the N type substrate bias variable type transistors 326 is connected to the common P type shallow well region 315 via a region 322 of higher P type dopant level. Therefore, region 322 is considered "body contact region") disposed in the layer; and a resistance region 333 (col. 21, line 63). Note that the isolation region is used to isolate the transistors and can function as resistance) disposed in the layer between the first transistor and the body contact region to substantially electrically isolate the first

Art Unit: 2815

transistor from the body contact region, the resistance region having a resistivity higher than a resistivity of the layer.

The resistance region 333 is formed of oxide (col. 21, lines 63-65), which inherently has a resistivity higher than a resistivity of the layer, which is doped with P type (col. 21, line 44).

Regarding claim 2, Iwata et al. discloses in figure 10 a second transistor 326 (col. 21, line 60) disposed in the layer, wherein the second transistor is disposed on a same side of the resistance region 333 as the body contact region 322.

Regarding claim 3, Iwata et al. teaches that the first conductivity type is p-type (col. 21, line 44). The phrase "the body contact region is adapted to be coupled to ground" is merely the intended use. Further since applicant does not define the structure and voltage level of ground, the well bias input 330 herein is considered "ground".

Regarding claim 5, Iwata et al. discloses on figure 10 a substrate 311 (col. 21, line 43), the layer 315 being disposed on top of the substrate.

Regarding claim 6, Iwata et al. discloses the resistance region 333 is formed of oxide (col. 21, lines 63-65), which has no impurity concentration; and the layer 315 is P doped (col. 21, line 44), which has some impurity concentration. Therefore, the resistance region has an impurity concentration lower than an impurity concentration of the layer.

Regarding claim 8, Iwata et al. discloses on figure 10 the resistance region 333 occupies substantially an entire cross sectional area of the layer 315 between the first transistor 327 and the body contact region 330.

Regarding claim 26, Iwata et al. discloses on figure 17 a device comprising a layer 314 of a first conductivity type (col. 22, line 14) formed directly on a semiconductor substrate 312; a first transistor 328 (col. 23, line 54) disposed in the layer 314; a body contact 321 (col. 22, lines 31-32) disposed in the layer; and a resistance region 316 (col. 2, line 10) disposed in the layer between the first transistor and the body contact region, the resistance region having a resistivity higher than a resistivity of the layer, wherein the substrate is of said first conductivity type (col. 2, line 8).

The term "substrate" is merely a label. Therefore element 312 has a similar structure as that of the substrate 210 of the instant application is considered "substrate" herein.

Regarding claim 27, Iwata et al. discloses on figure 17 the resistance region 316 substantially isolates the first transistor 328 from the body contact region 321.

Regarding claim 28, Iwata et al. discloses on figure 17 a second transistor 325 (col. 23, line 53) disposed in the layer, wherein the second transistor is disposed on a same side of the resistance region as the body contact region 321.

Regarding claim 29, Iwata et al. discloses on figure 17 the body contact region 321 is adapted to be coupled to ground. Note that the body contact region 321 is coupled to bias input 329 (col. 22, line 29), which is considered "ground" herein.

Regarding claim 31, Iwata et al. discloses the resistance region 316 has an impurity concentration lower than an impurity concentration of the layer (see rejection of claim 6 above).

Regarding claim 33, Iwata et al. discloses on figure 17 the resistance region 316 occupies substantially an entire cross sectional area of the layer between the first transistor 328 and the body contact region 321.

Regarding claim 38, Iwata et al. discloses on figure 10 a device comprising:

- a layer of a first conductivity type 315 (col.21, line 44);
- a first transistor 327 disposed in the layer (col. 21, line 51);
- a body contact region 322 disposed in the layer;

a second transistor 326 disposed in the layer, wherein the second transistor is disposed on a same side of the resistance region as the body contact region; and a resistance region 333 disposed in the layer between the first transistor 327 and the body contact region, the resistance region having a resistivity higher than a resistivity of the layer, wherein the resistance region has an impurity concentration lower than an impurity concentration of the layer (see rejection of claim 6 above).

Regarding claim 39, Iwata et al. discloses on figure 10 a substrate 311, the layer 315 being disposed on top of the substrate.

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

Art Unit: 2815

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

Claim 4 is rejected under 35 U.S.C. 103(a) as being unpatentable over Iwata et al.

Regarding claim 4, Iwata discloses on figure 10 the body contact region 330 is coupled to a power supply 330. Further, Iwata et al. teaches the first conductivity type is p type, *not n type* as claimed. However, it is well known in the art that n type and p type can be interchanged, merely depending upon certain application and design. Therefore, it would have been obvious to one of ordinary skill in the art at the time the invention was made to modify Iwata et al. by having the first conductivity type being n type for the purpose of providing certain application and design of a semiconductor device.

Claims 7 and 32 are rejected under 35 U.S.C. 103(a) as being unpatentable over Iwata et al in view of Yamaguchi et al. (US 6,867,106 B2)

Regarding claims 7 and 32, Iwata et al. discloses on figure 10 substantially all the structure set forth in the claimed invention except a discrete capacitor coupled between a body and a source of the first transistor. However, Yamaguchi et al. discloses on figure 3 a discrete capacitor coupled between a body and a source of the first transistor (col. 8, lines 21-26). In view of such teaching, it would have been obvious to one of ordinary skill in the art at the time the invention was made to modify Iwata et al. by having a discrete capacitor coupled between a body and a source of the first transistor

Art Unit: 2815

for the purpose of suppressing performance deterioration of the transistors (col. 3, lines 16-17 of Yamaguchi et al.).

Claims 14, 30, 35, 36, 40 and 41 are rejected under 35 U.S.C. 103(a) as being unpatentable over Iwata et al in view of Wong et al. (US 6,246,094 B1).

Regarding claims 14, 30, 35, 36 and 40, Iwata et al. discloses on figure 10 substantially all the structure set forth in the claimed invention except the layer being epitaxial layer. However, Wong et al. discloses on figure 2D the layer 14 being epitaxial layer (col. 4, line 67 and col. 5, line 1). In view of such teaching, it would have been obvious to one of ordinary skill in the art at the time the invention was made to modify Iwata et al. by having the layer being epitaxial layer for the purpose of preventing latch up in a CMOS integrated circuit (col. 1, lines 10-12).

Regarding claim 41, Iwata et al. discloses the resistance region 333 is formed of oxide (col. 21, lines 63-65), which has no impurity concentration; and the layer 315 is P doped (col. 21, line 44), which has some impurity concentration. Therefore, the resistance region has an impurity concentration lower than an impurity concentration of the layer.

Allowable Subject Matter

Claims 9-13 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

The following is a statement of reasons for the indication of allowable subject matter: The reference (s) of record do not teach or suggest, either singularly or in combination at least the limitation of "a second transistor coupled in series with the first transistor and having a control electrode adapted to receive an input signal of the device, the first transistor having a control electrode adapted to receive a bias voltage, and the body contact region being adapted to be coupled to a first one of power supply voltage and ground; and a load having a first end coupled to the first transistor and a second end adapted to be coupled to a second one of the power supply voltage and ground, a body of the second transistor being adapted to be coupled to the first one of the power supply voltage ground" for claim 9.

Response to Arguments

Applicant's arguments with respect to claims 1-8, 14, 26-33, 35-36 and 38-41 have been considered but are moot in view of the new ground(s) of rejection.

Conclusion

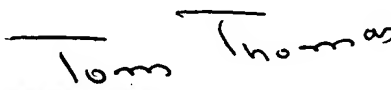
Any inquiry concerning this communication or earlier communications from the examiner should be directed to Joseph Nguyen whose telephone number is (571) 272-1734. The examiner can normally be reached on Monday-Friday, 7:30 am- 4:30 pm. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Tom Thomas can be reached on (571) 272-1664. The fax phone number for

Art Unit: 2815

the organization where this application or proceeding is assigned is (703) 872-9306 for regular communications.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

JN
May 25, 2005


TOM THOMAS
SUPERVISORY PATENT EXAMINER